

# REPORT DOCUMENTATION PAGE

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MEMORANDUM FOR PRS (In-House Contractor Publication)

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08 May 2002

SUBJECT: Authorization for Release of Technical Information, Control Number: **AFRL-PR-ED-VG-2002-101**  
Tim Haddad (ERC) and Brent Viers (PRSM), "Organic Polymers Modified with Inorganic Polyhedra"

**Canadian Society for Chemistry  
(2-5 June 2002, Vancouver, Canada) (Deadline: 31 May 2002)**

**(Statement A)**

## ORGANIC POLYMERS MODIFIED WITH INORGANIC POLYHEDRA.

Timothy S. Haddad and Brent D. Viers  
ERC Inc., Air Force Research Lab,  
10 E Saturn Boulevard  
Edwards Air Force Base, CA 93524

Nanostructured composites of thermoplastics and inorganic clusters have been developed by incorporating polyhedral oligomeric silsesquioxane (POSS) macromers into organic polymers. These hybrid inorganic/organic thermoplastics based on styrenes, acrylics, imides, norbornenes or siloxanes, are reinforced by covalently linking monodisperse inorganic POSS clusters to the polymer backbone. A typical POSS-macromer, R<sub>7</sub>P(Si<sub>8</sub>O<sub>12</sub>), is a well-defined octomeric polyhedron containing a single "P" functionality for polymerization and seven "R" groups to solubilize and compatibilize the inorganic filler with the organic matrix. A nanoreinforcement effect from the POSS groups is strongly influenced by the seven "R" groups (cyclopentyl, cyclohexyl, isobutyl or phenyl). Covalently attached POSS groups result in significant change to the observed characteristic relaxation time of the polymer; rheological measurements on molten polymer indicate that interactions between the POSS groups generate a reversible network material with rubbery properties. TEM images show that the inorganic POSS moieties associate to form a nanoscale network within the polymer matrix.

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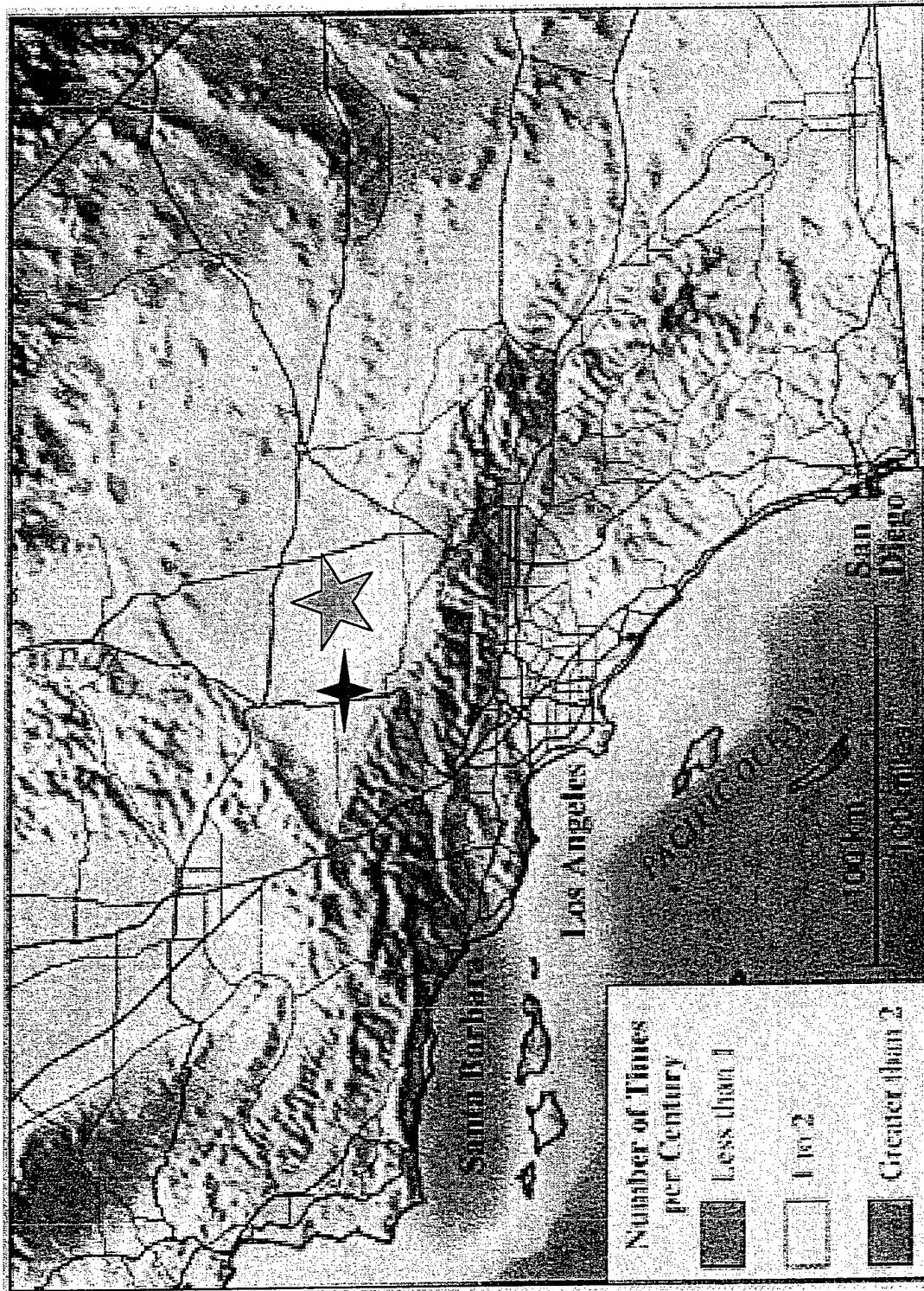
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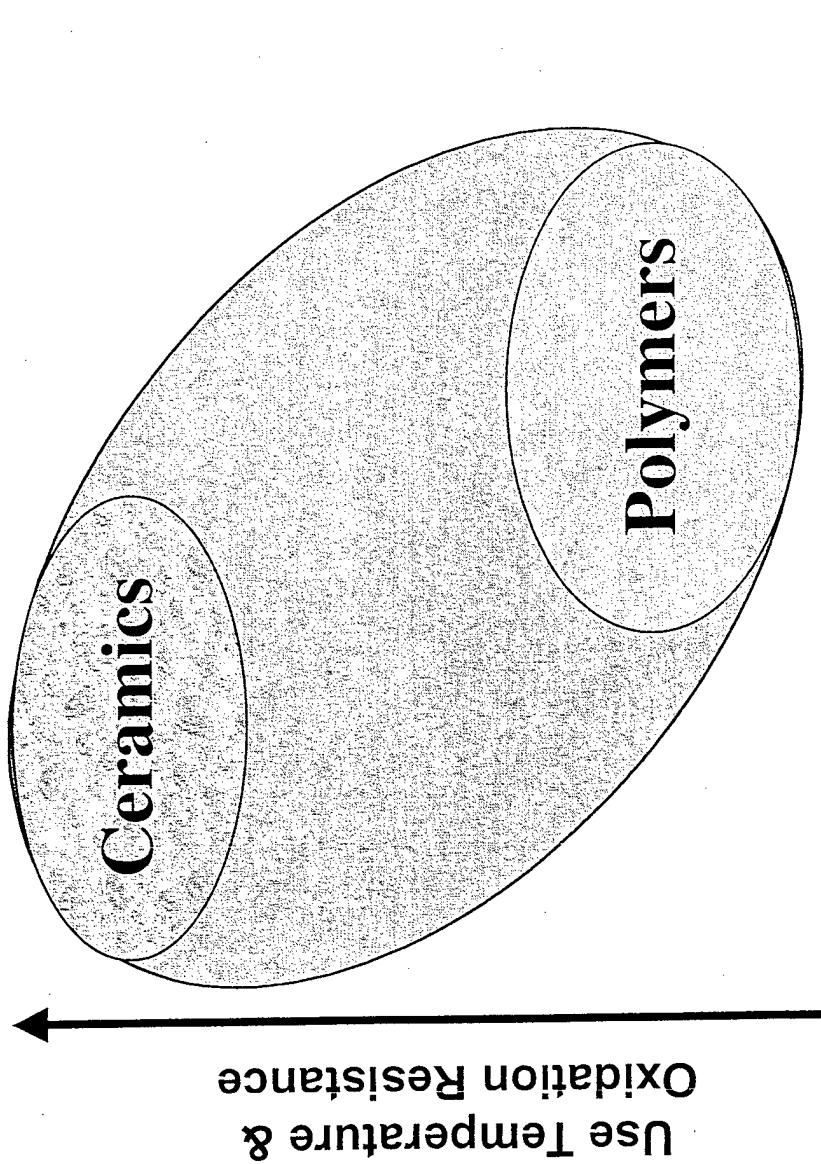
# ORGANIC POLYMERS MODIFIED WITH INORGANIC POLYHEDRA

Tim Haddad and Brent Viers  
ERC Inc., Air Force Research Lab

# Edwards Air Force Base, CA



## Hybrid Inorganic/Organic Polymers



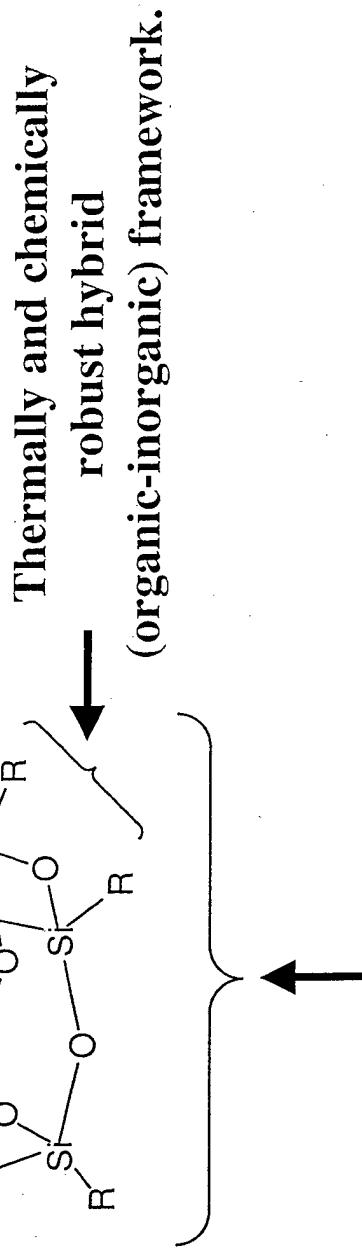
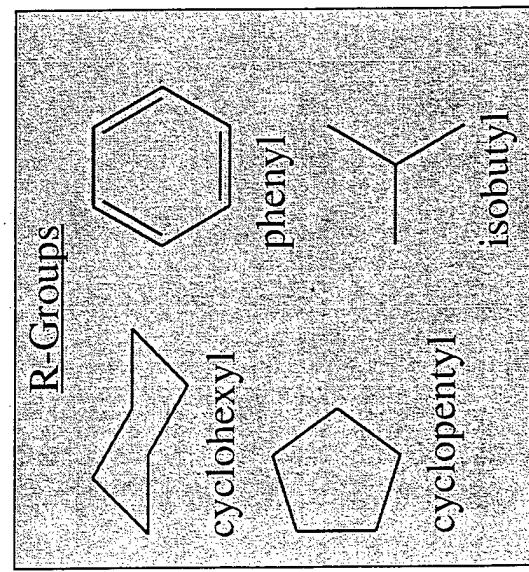
Hybrid plastics can bridge the differences between ceramics and polymers

# Anatomy of a POSS Macromer

Nonreactive organic (R) → Nonreactive organic (R)  
groups for solubilization  
and compatibilization.

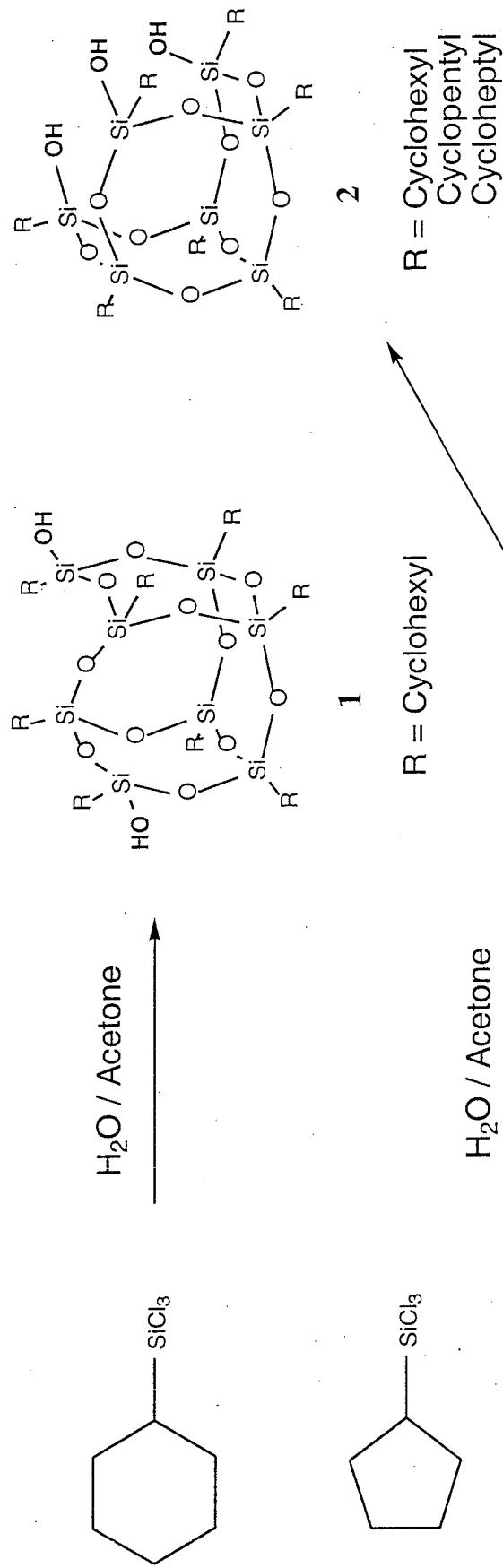


Nanoscopic in size with an Si-Si distance of 0.5 nm and a R-R distance of 1.5 nm.



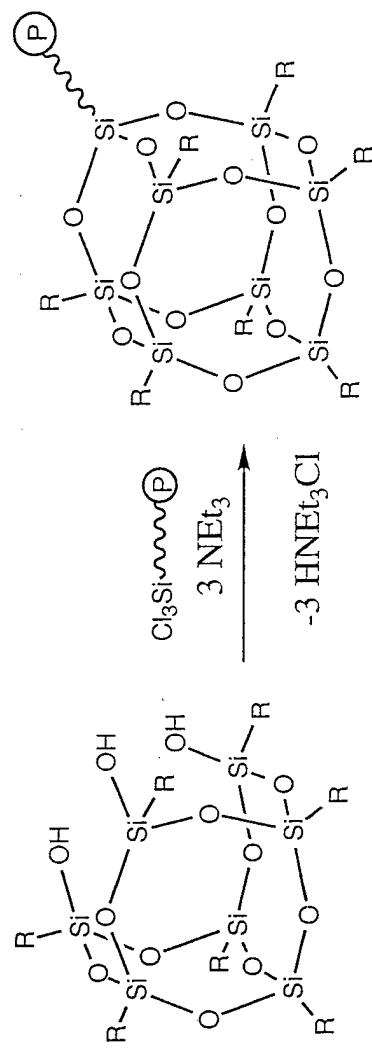
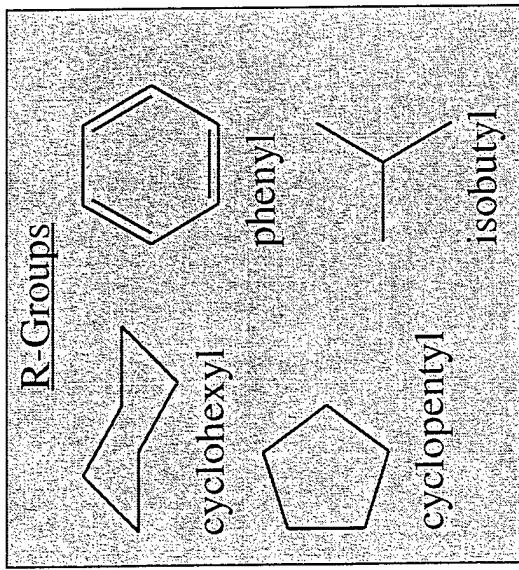
Precise three-dimensional structure for molecular level reinforcement of polymer segments and coils.

# POSS Silanol Synthesis



Brown & Vogt: JACS, 1965, p. 4313  
 Feher et al: JACS, 1989, p 1741;  
 Organometallics, 1991, p 2526

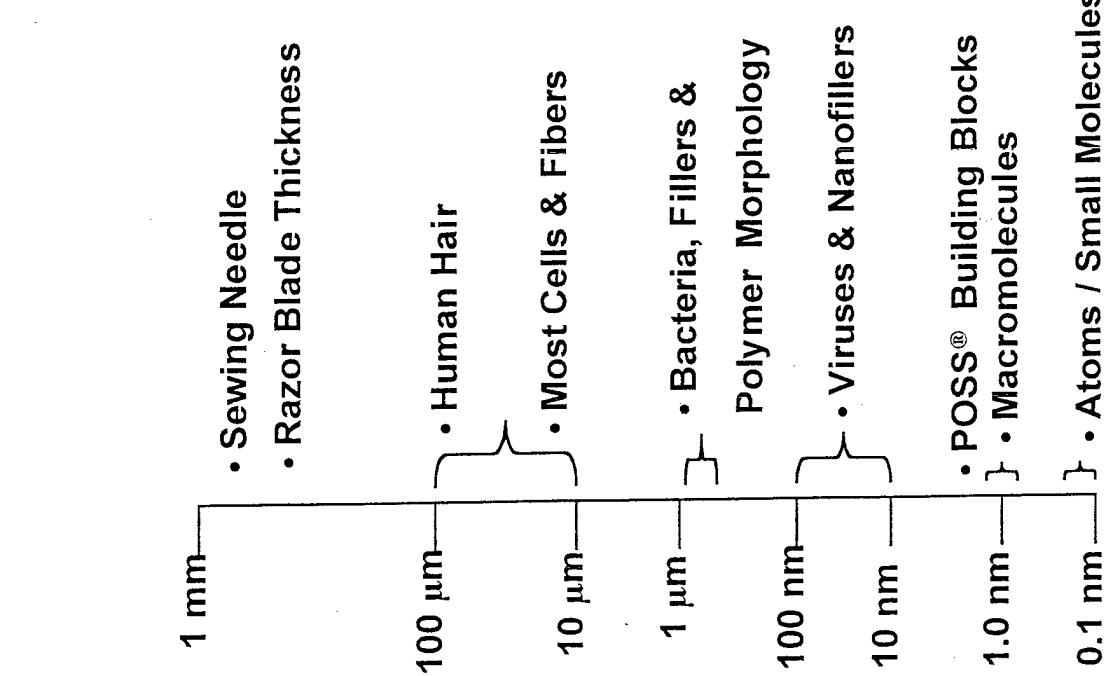
# POSS Macromers For Nanocomposites



Halides	Nitriles	Styryls
Alcohols	Amines	$\alpha$ -olefins
Esters	Isocyanates	Acrylics
Bisphenols	Epoxides	Norbornenyls

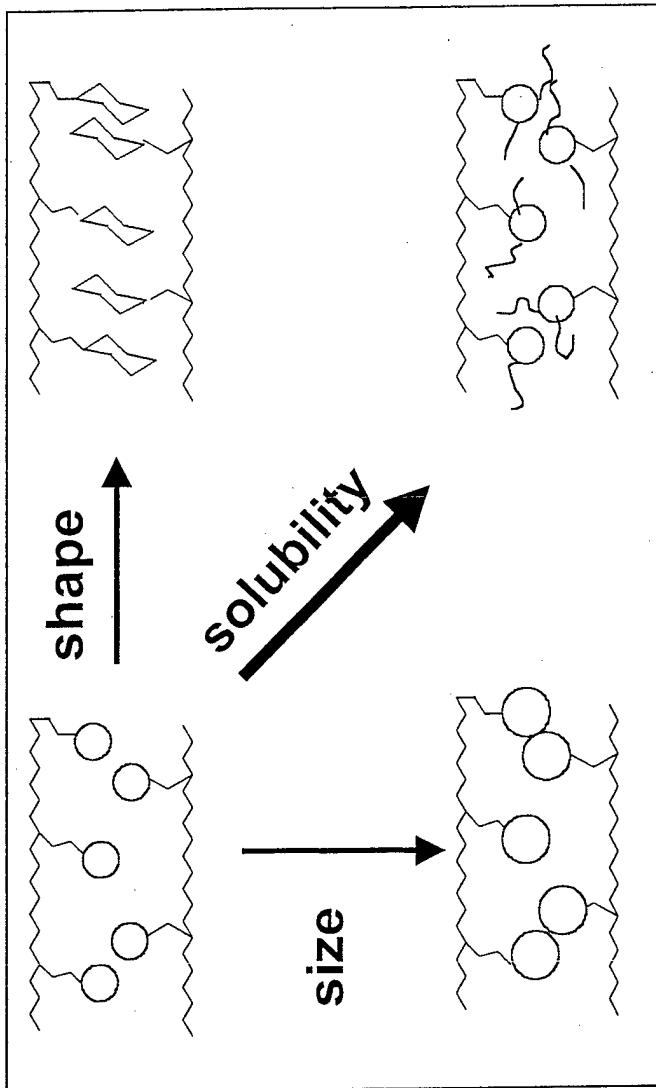
POSS-based macromers are now available through either **Gelest** or **Aldrich**  
POSS technology is commercialized by **Hybrid Plastics** in Fountain Valley CA

# Why POSS and Why Nano?



Field	Property	Critical Length
Electronics	Tunneling	1-100 nm
Optical	Quantum Well	1-100 nm
	Wave Decay	10-1000 nm
Polymers	Primary Structure	0.1-10 nm
	Secondary Structure	10-1000 nm
Mechanics	Dislocation Interaction	1-1000 nm
	Crack Tip Radius	1-100 nm
	Entanglement Rad.	10-50 nm
Therm-Mech.	Chain Motion	0.5-50 nm
Nucleation	Defect	0.1-10 nm
	Critical Nucleus Size	1-10 nm
Catalysis	Surface Topology	1-10 nm
Biology	Cell Walls	1-100 nm
Membranes	Porosity Control	0.1-5 nm

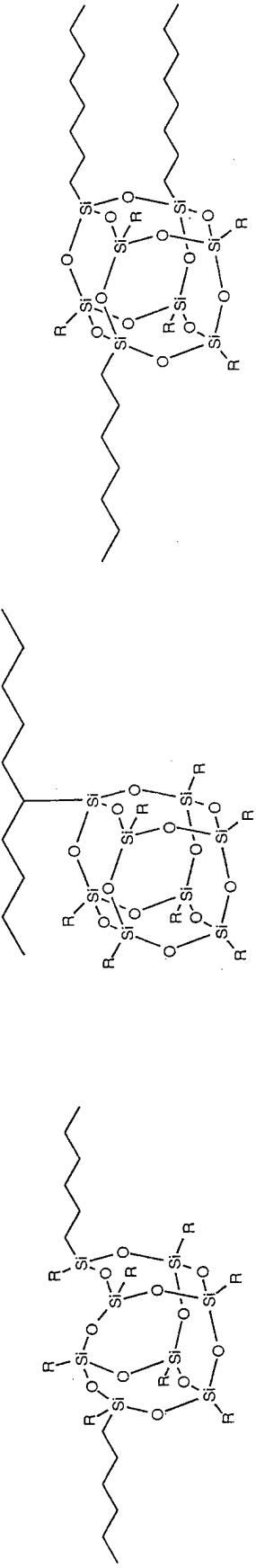
# Structure-Property Relationships



- Maximizing property enhancements through changes at the nano level

- Polymer miscibility vs. POSS/POSS interactions

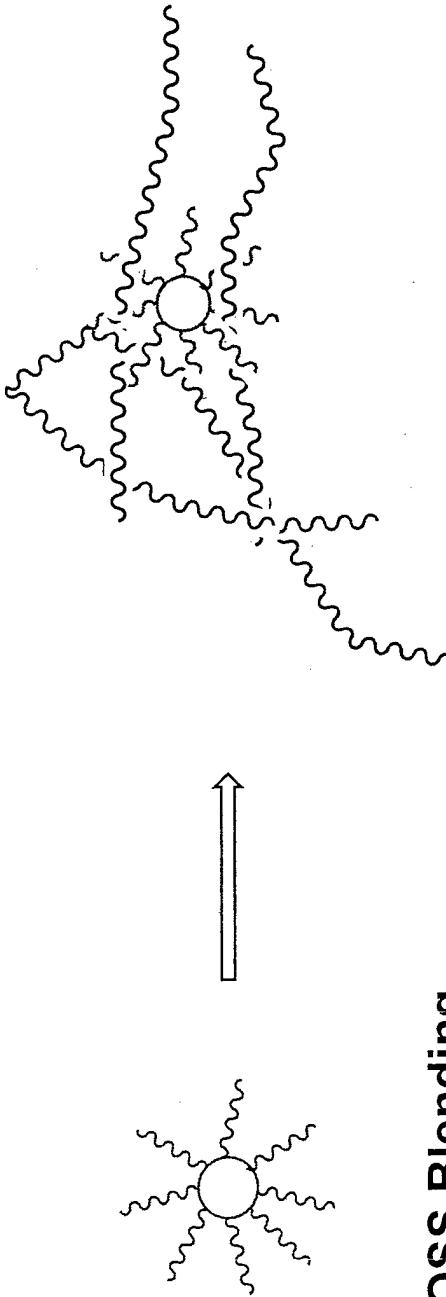
# POSS Polymer Incorporation



POSS Bead

POSS Pendant

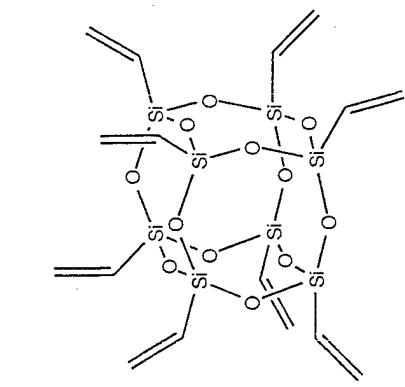
POSS Crosslinking



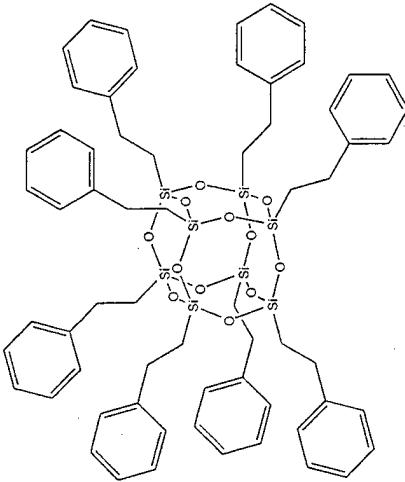
POSS Blending

**Size & Shape**

**50 Wt % POSS Blends in 2 Million MW Polystyrene**



Vi<sub>8</sub>T<sub>8</sub>

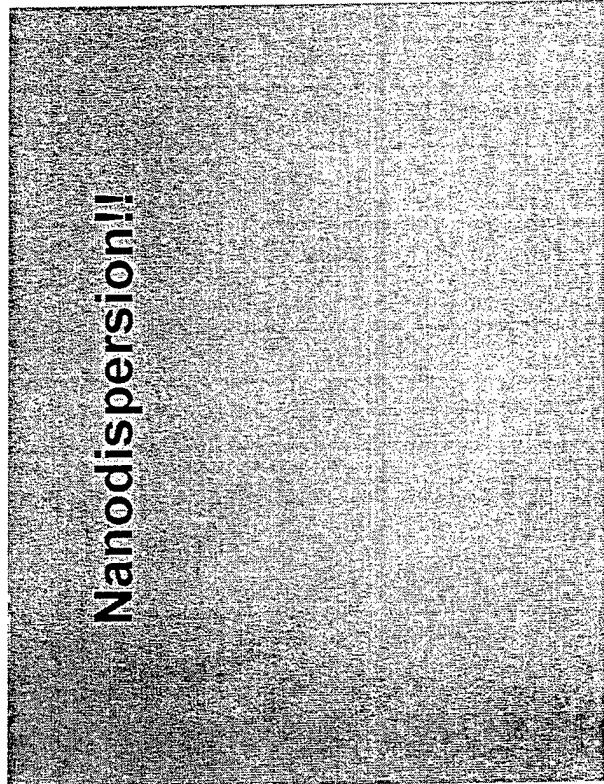


Phenethyl<sub>8</sub>T<sub>8</sub>

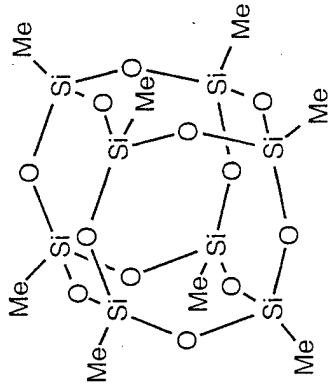
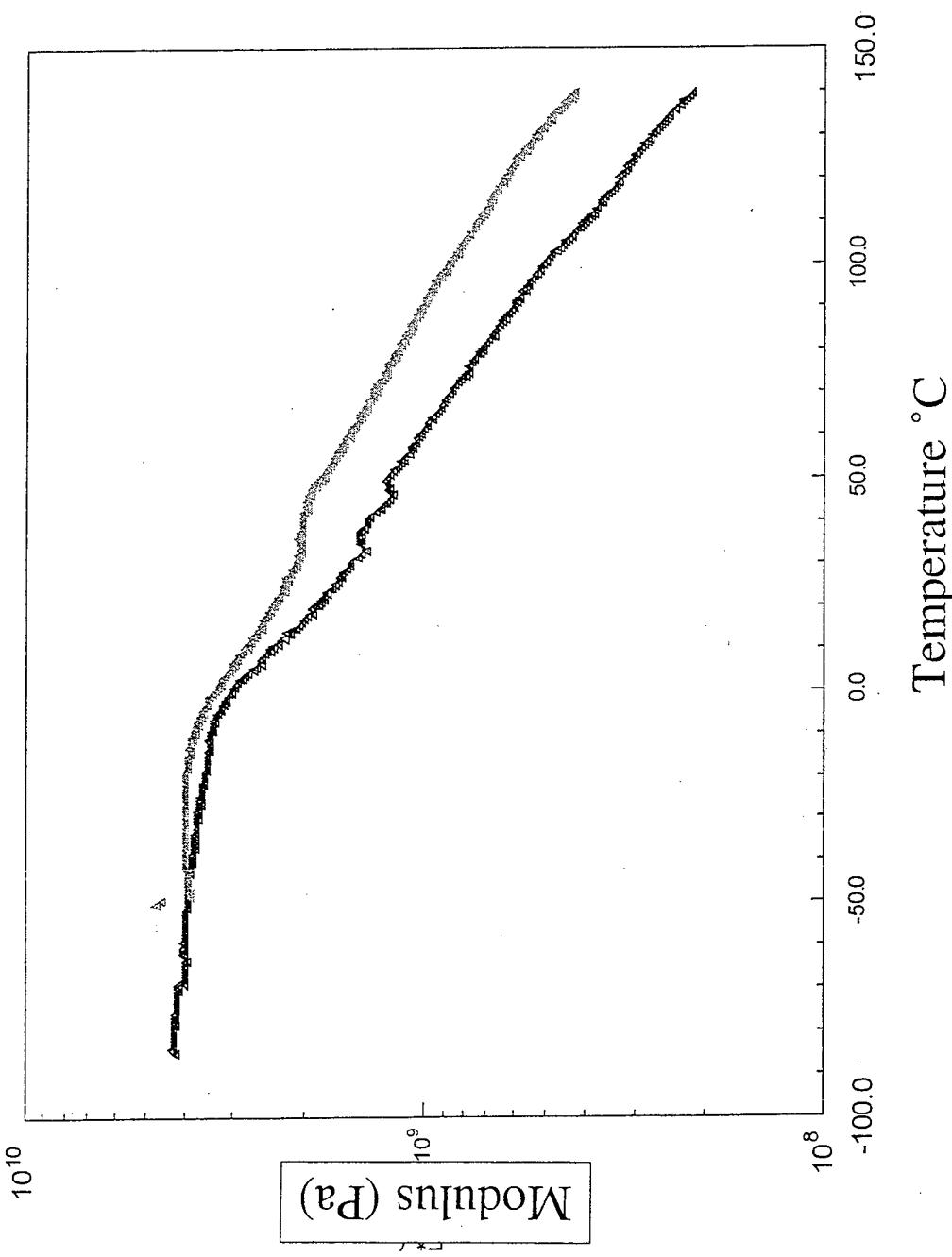


Nanodispersion!!

1 μm

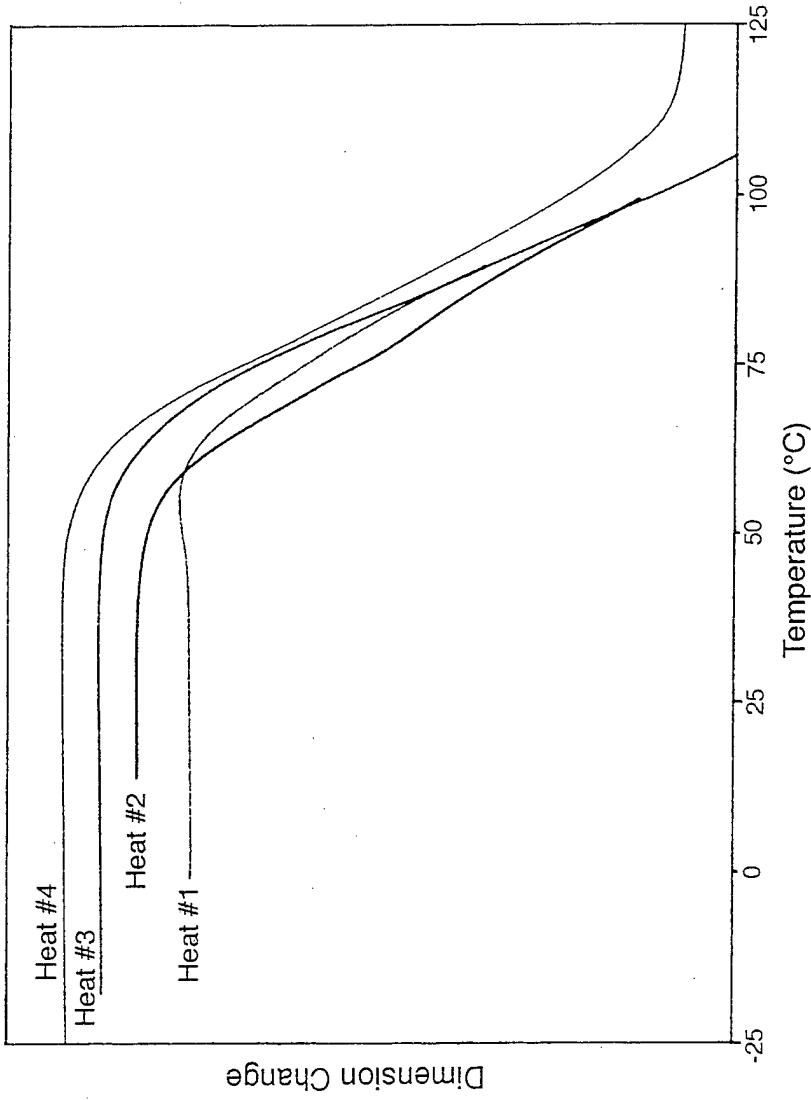
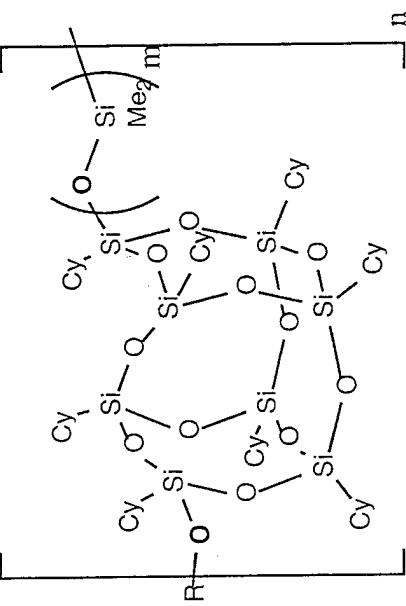


# DMA of 10 Wt % POSS in isotactic Polypropylene

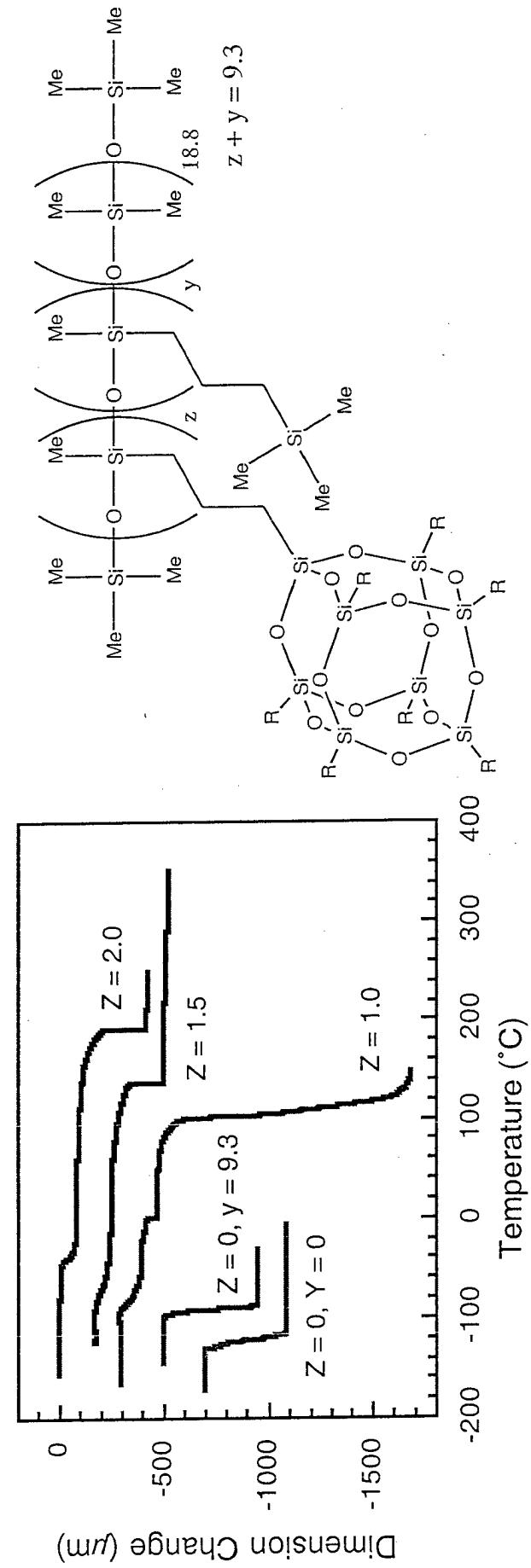


# PDMS-POSS-TMA Characterization

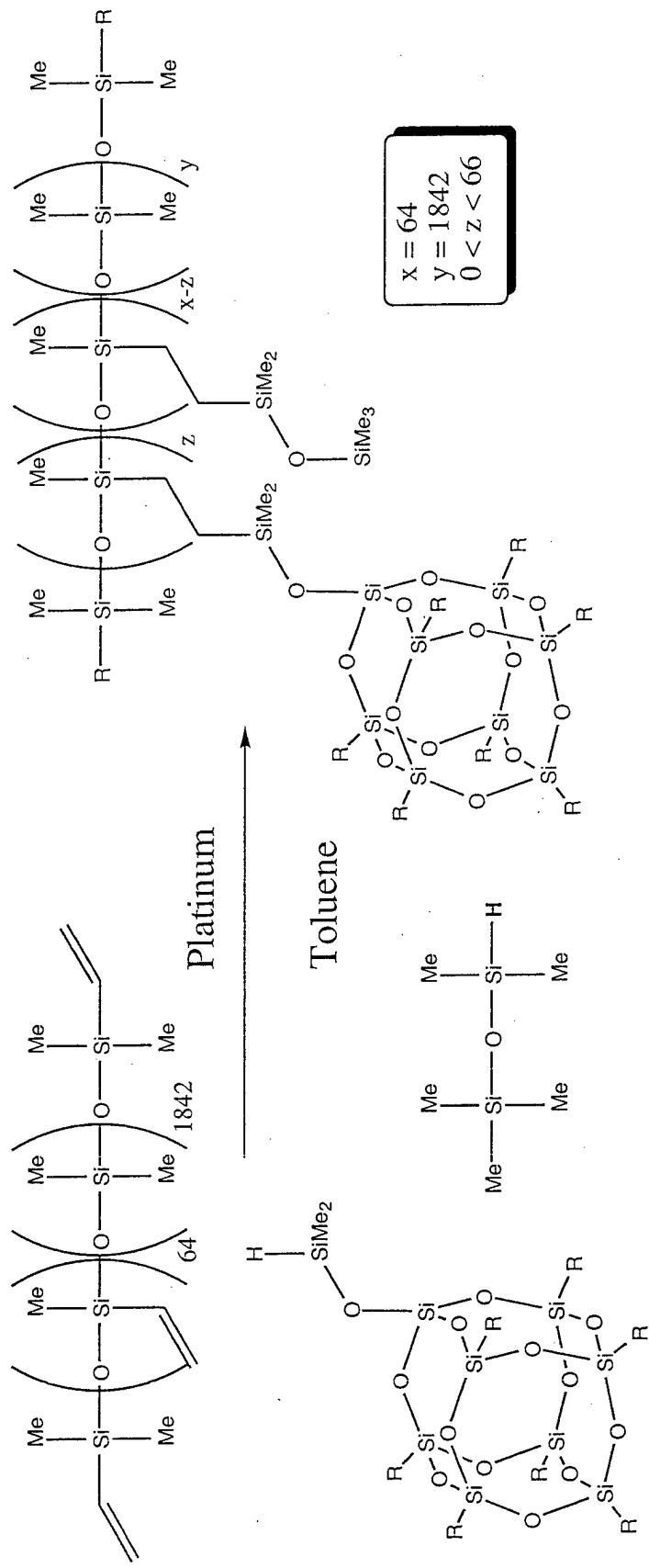
The POSS/Siloxane copolymers with four or more Si-O repeat units in the siloxane segment have softening temperatures well below the decomposition temperatures.



# TMA of Pendant POSS-Siloxanes



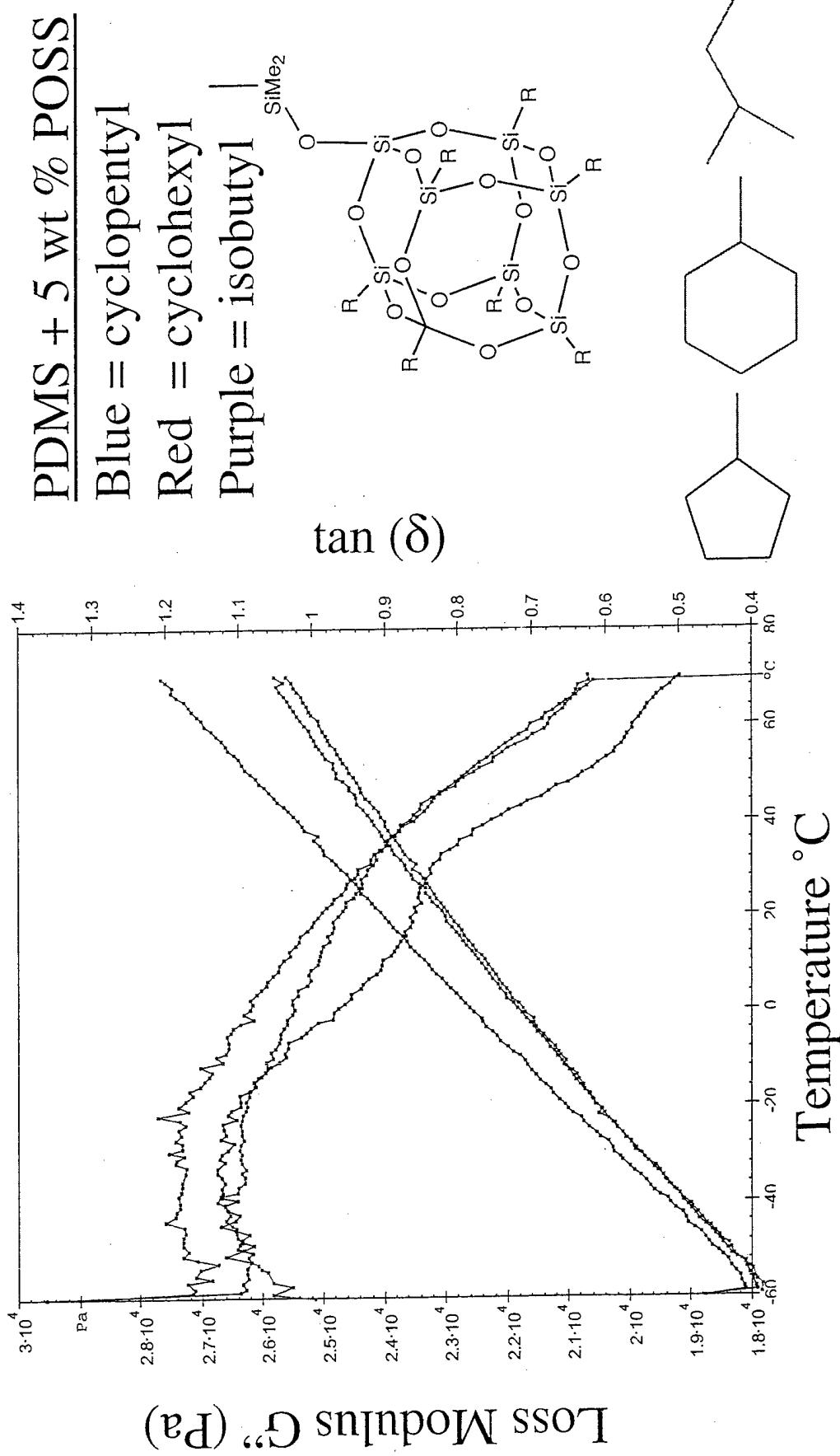
# Hydrosilation to High MW PDMS



Used 5 weight % POSS

There are about 7 POSS-macromers per PDMS chain

Comparison of Three T<sub>8</sub>-POSS Macromers



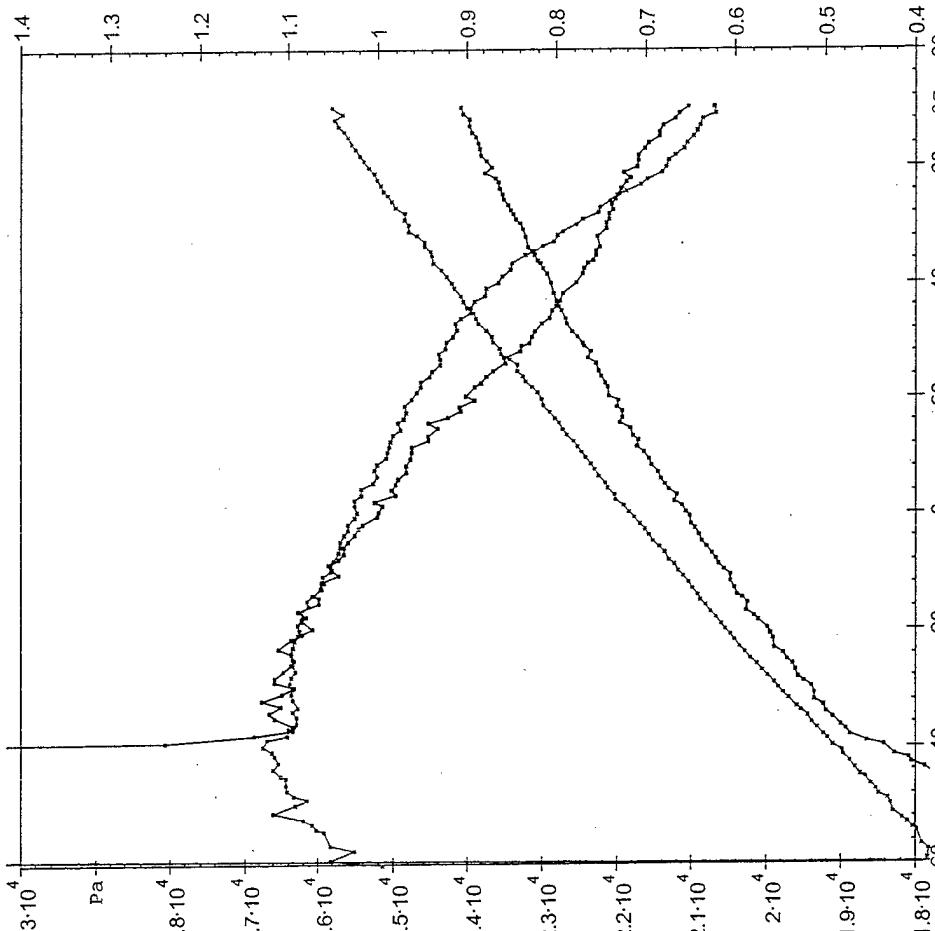
# Comparison of TWO POSS Polyhedra

PDMS + 5 wt %  
CyclohexylPOSS

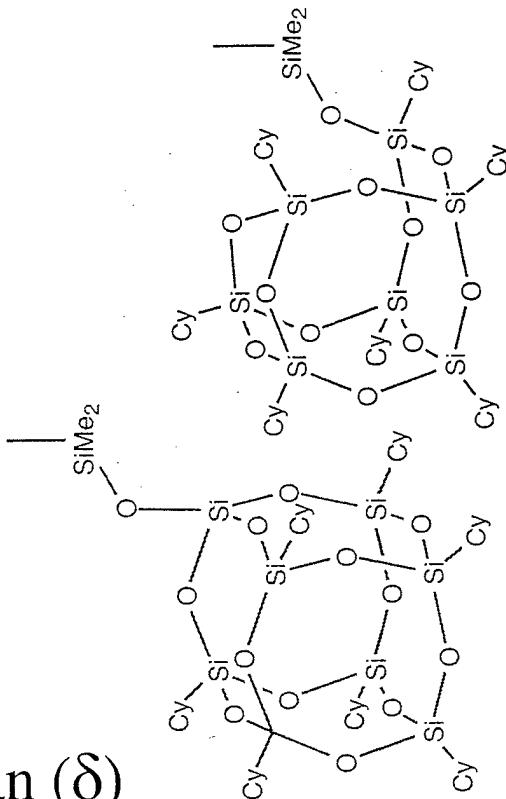
Red = T8-POSS

Blue = T7-POSS

$\tan(\delta)$

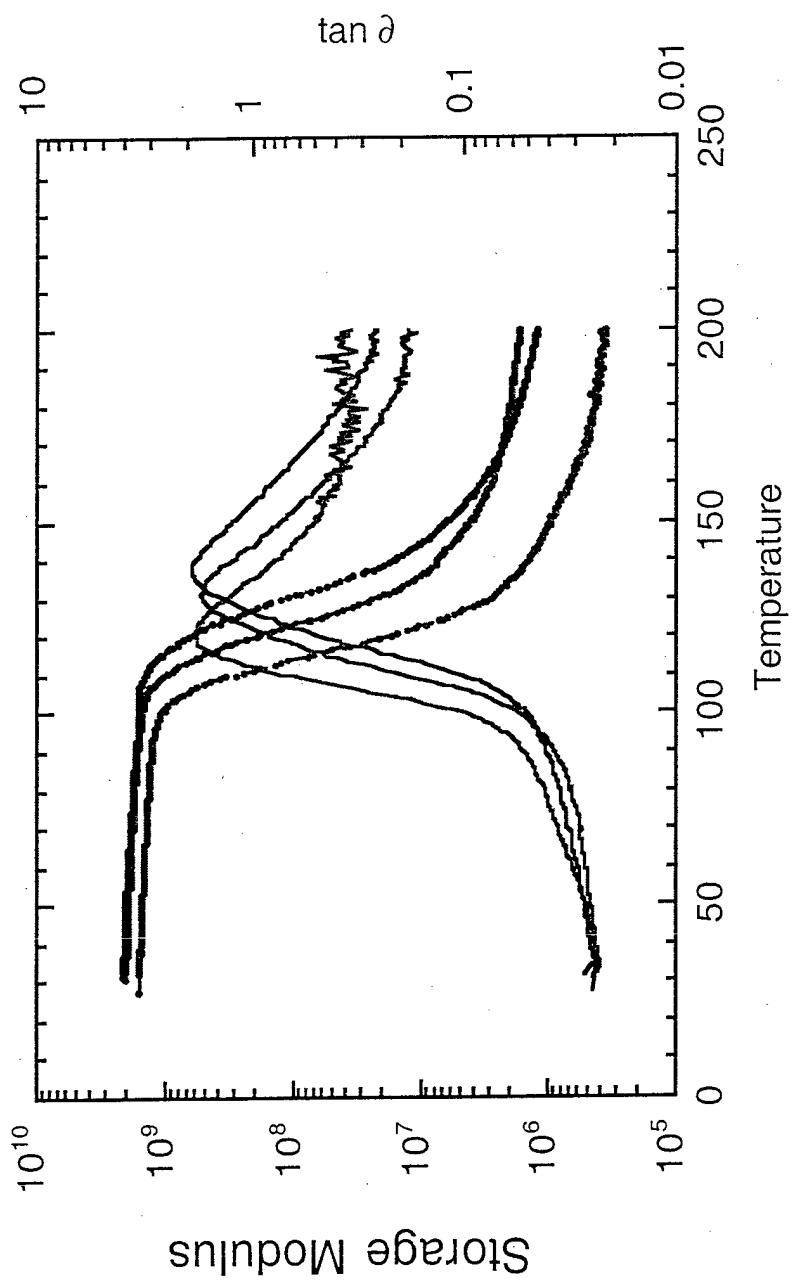


Loss Modulus  $G''$  (Pa)



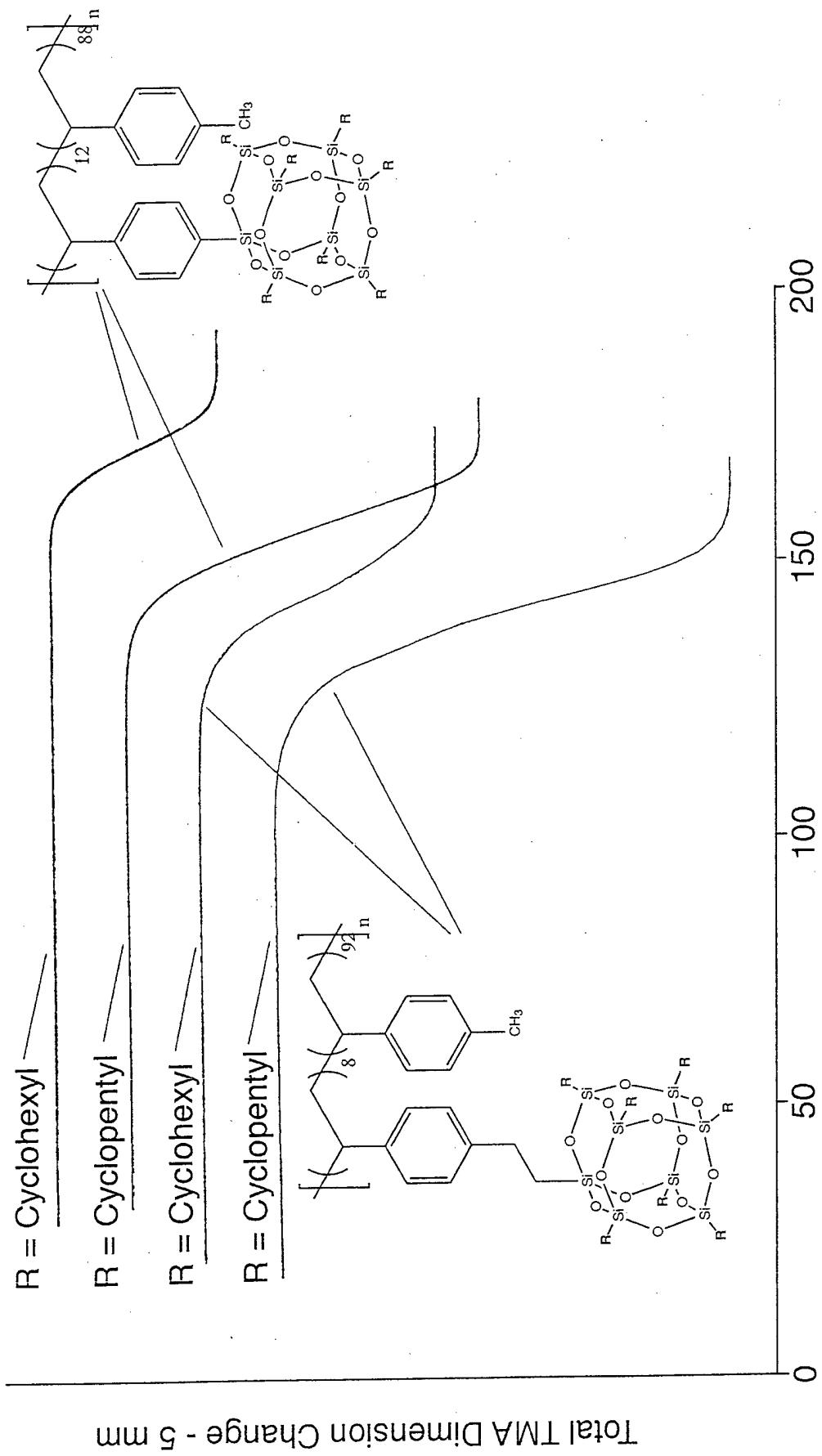
Temperature °C

# DMA of 30 wt % POSS Polystyrenes

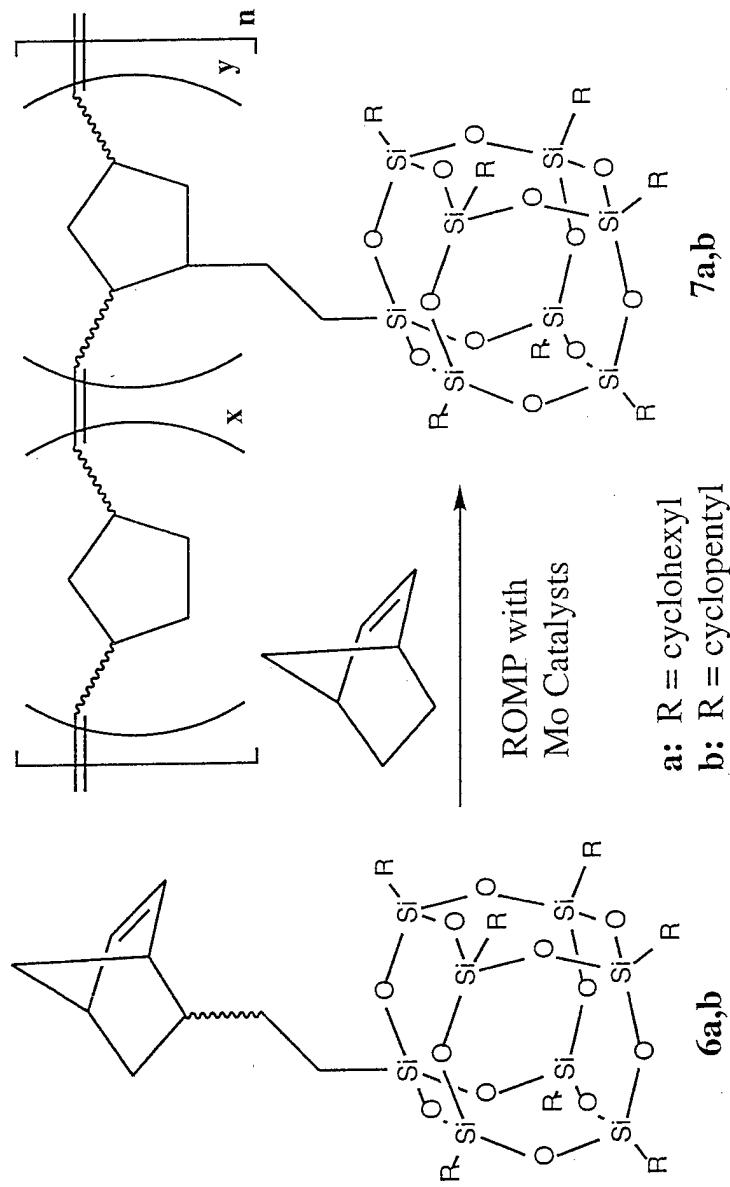


- Comparison of isobutyl, cyclopentyl & cyclohexyl
- Bulk polymerized samples

# TMA Plot Comparison For POSS-Styryl and POSS-EthyStyryl Polymers (R = Cyclohexyl and Cyclopentyl)



# Polymerization of POSS Norbornenes

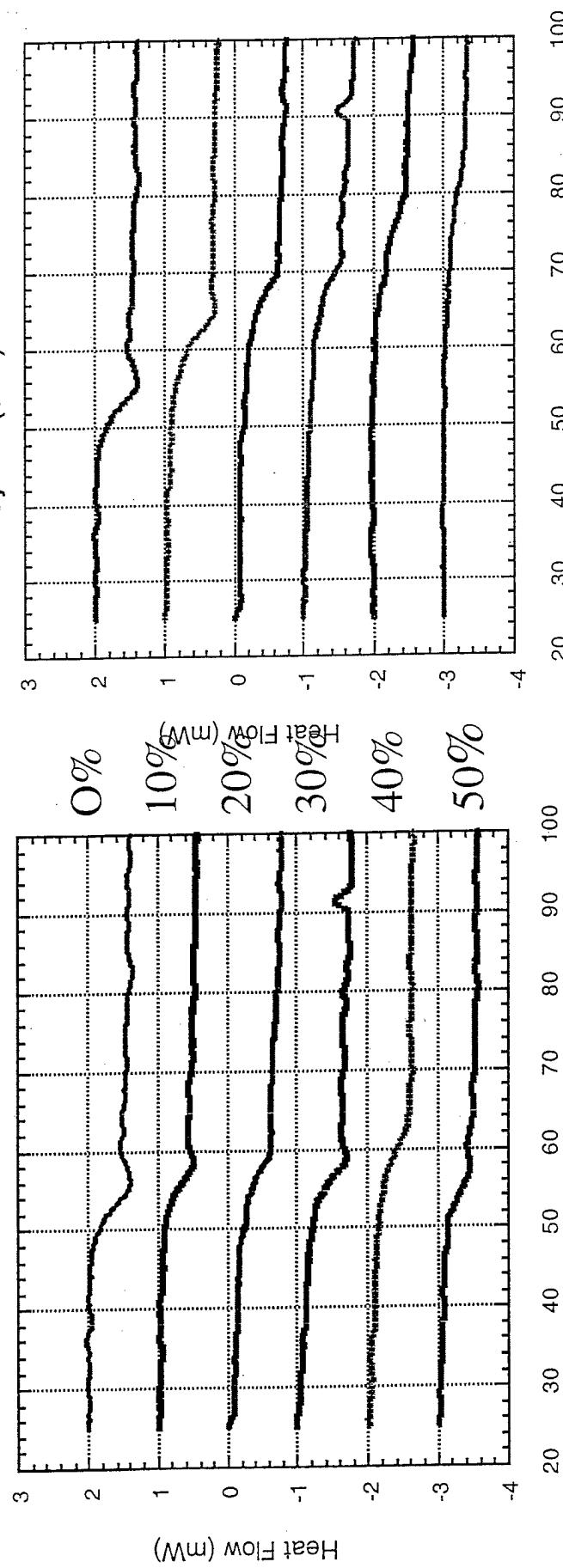


Both block and random copolymers were synthesized. The wt. % POSS was varied from 0 to 50 wt. % POSS. An ideal polymerization would yield polymers with 500 monomer units.

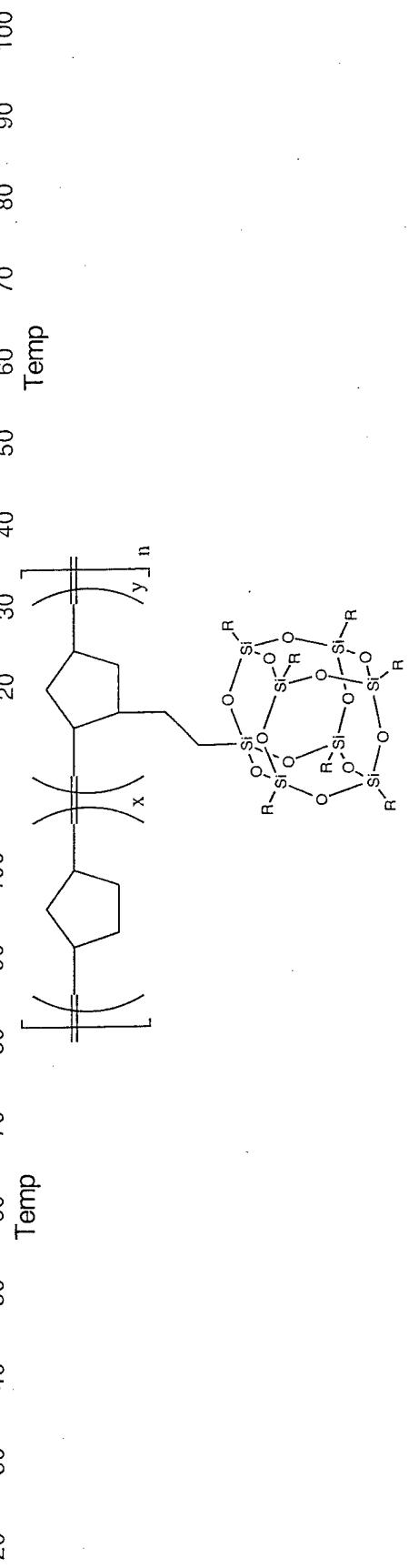
0 wt % POSS, 0 mole % POSS: x = 500, y = 0  
10 wt % POSS, 1 mole % POSS: x = 495, y = 5  
50 wt % POSS, 8 mole % POSS: x = 460, y = 40

# DSC Data for POSS-Norbornenes

CyNorb(0-50)-block

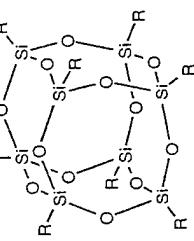
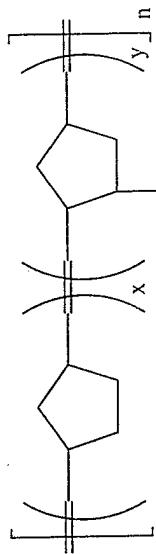
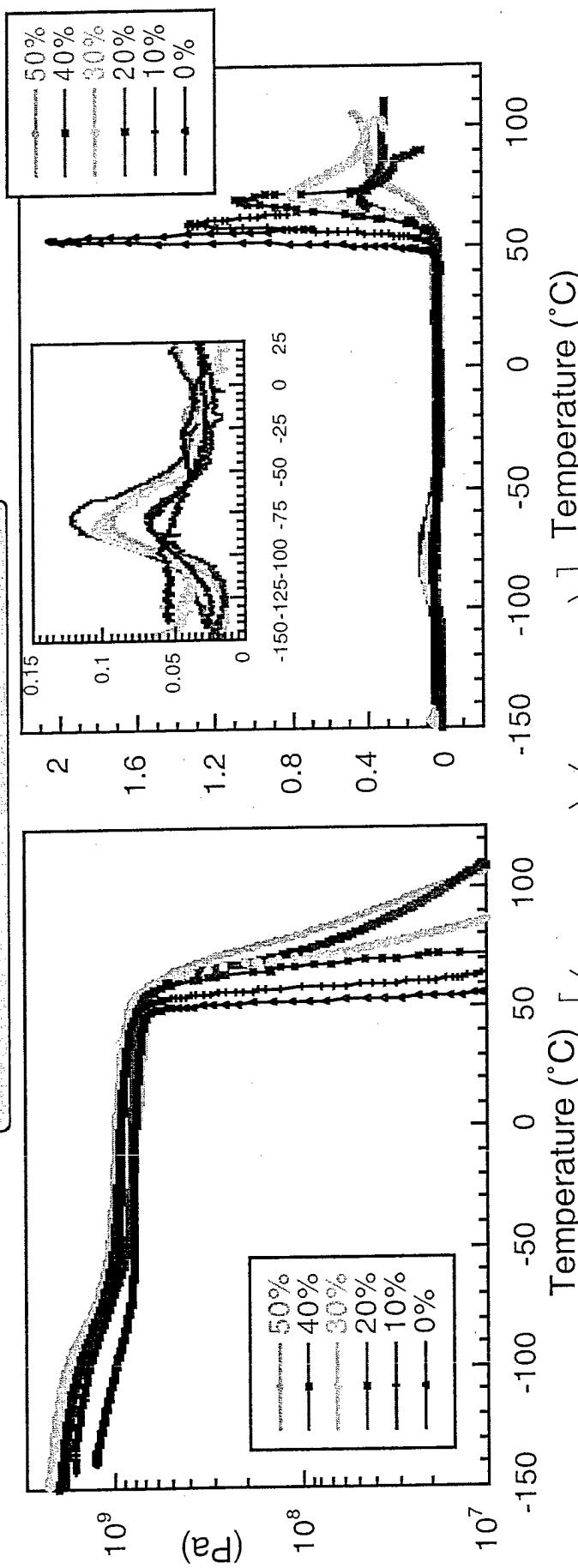


CyNorb(0-50)-random



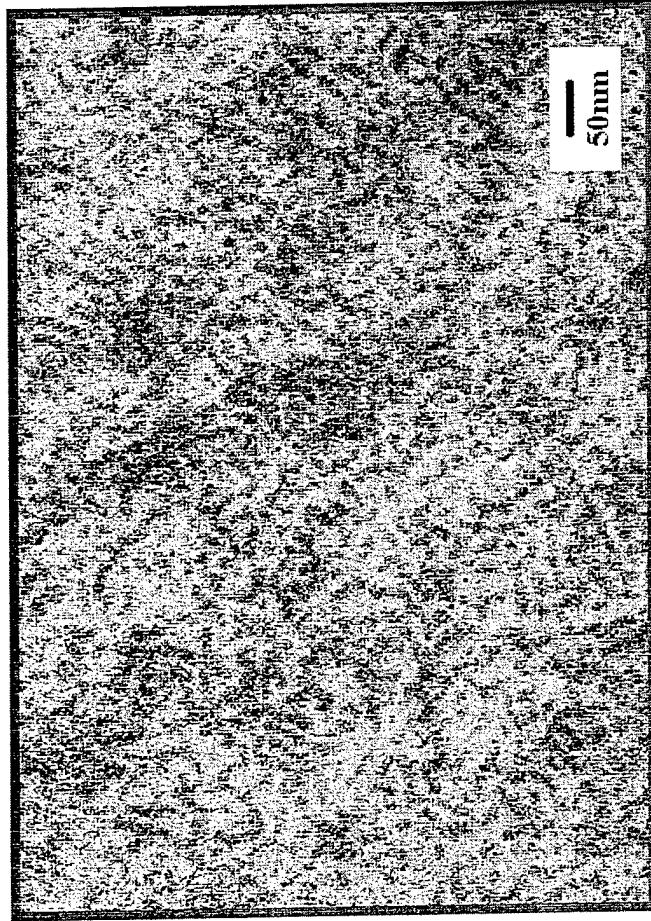
# Storage Modulus and Loss Tangent

Cyclohexyl Relaxation: 14.7 kcal/mol

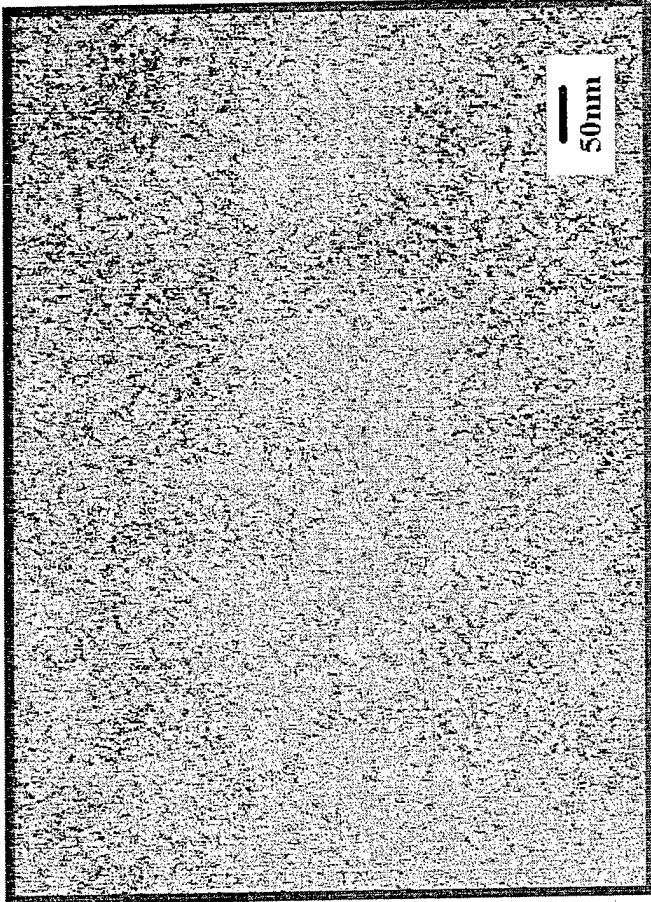


# TEM of Random POSS Norbornenes

50CyPOSS/PN



50CpPOSS/PN

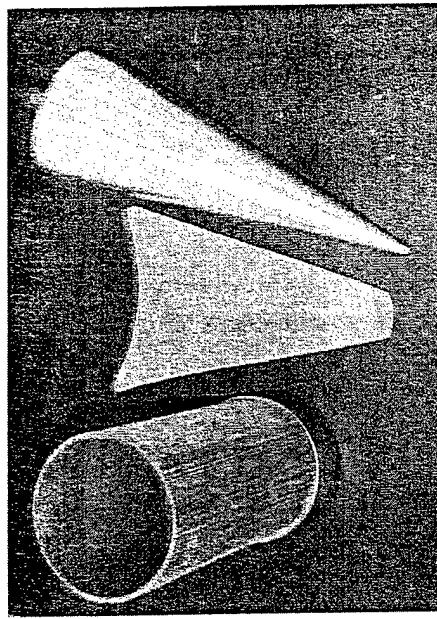


“Coarse” Cylinder Nanostructure  
(Diameter ~ 12nm)

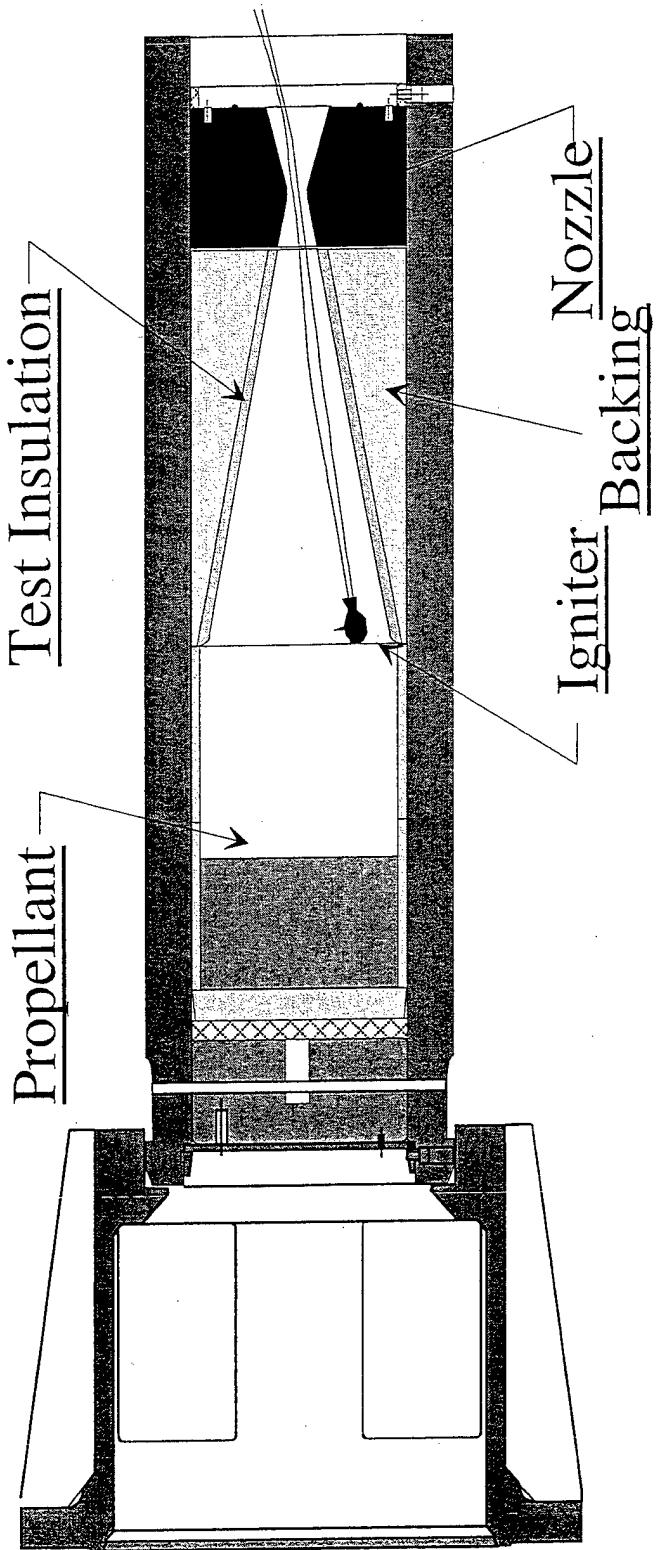
“Fine” Cylinder Nanostructure  
(Diameter ~ 6nm)

CyclohexylPOSS-rich domains may entrain more unoriented polynorbornene chains than CyclopentylPOSS-rich domains.

# Solid Rocket Motor Insulation



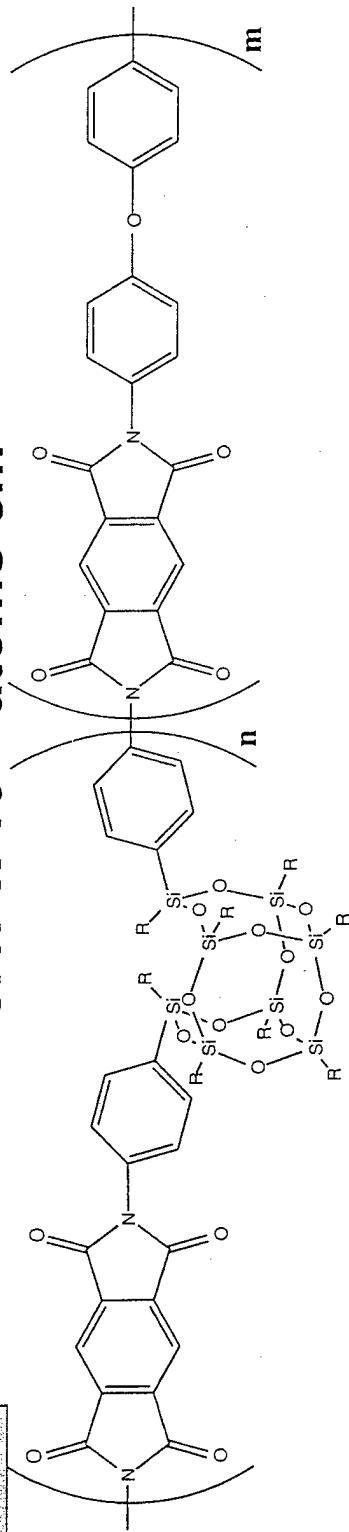
*POSS-Insulation Sample*





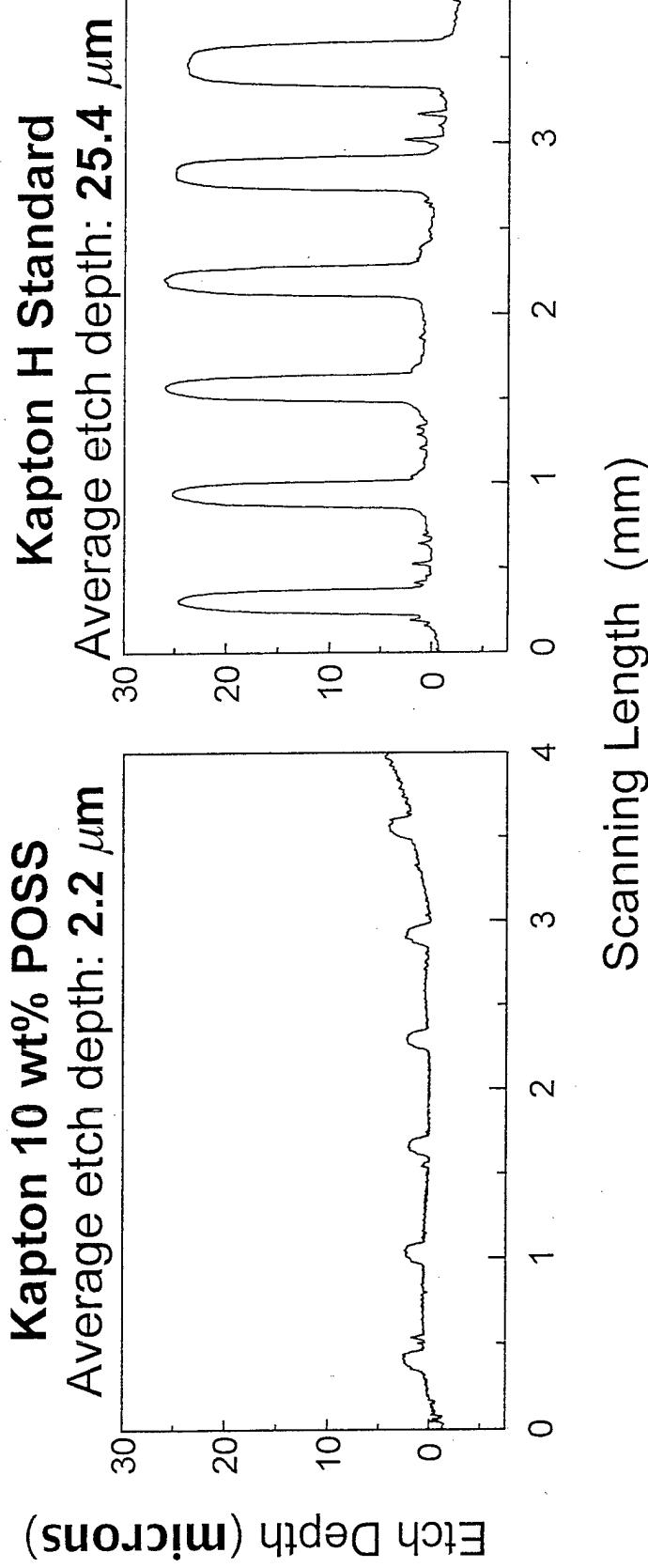
## O-Atom Etching Experiment

$8.47 \times 10^{20}$  atoms cm<sup>-2</sup>



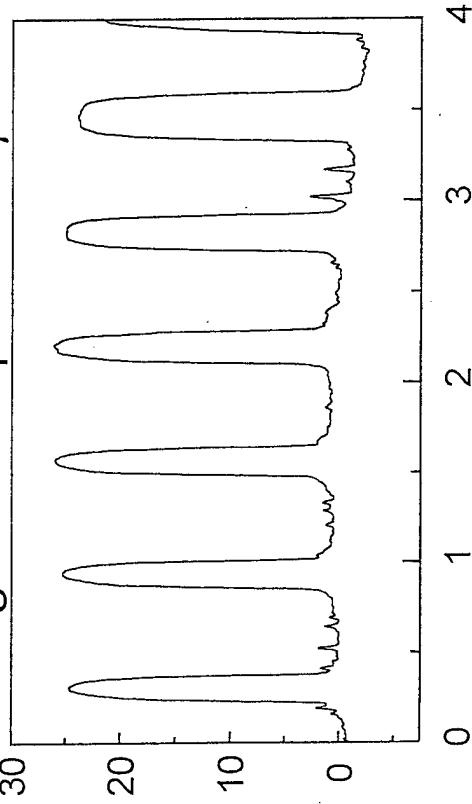
## Kapton 10 wt% POSS

Average etch depth: 2.2  $\mu\text{m}$



## Kapton H Standard

Average etch depth: 25.4  $\mu\text{m}$

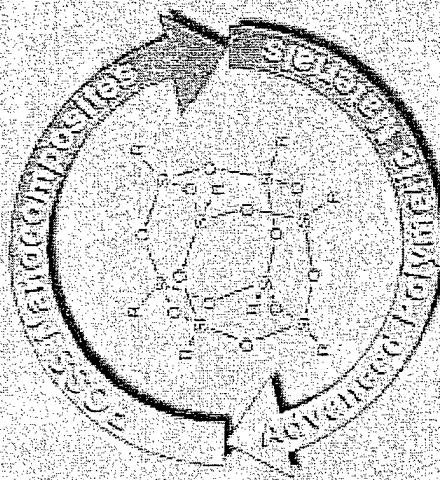


## Summary

- The successful incorporation of nano-sized inorganic clusters (POSS) into a wide variety of polymers has been demonstrated.
- These POSS clusters have a remarkable effect on the thermal transitions and mechanical properties of the polymers they are copolymerized into.
- The POSS effect on the properties of analogous polymers shows a dependency on the type of alkyl group on the POSS cluster.
- TEM images of randomly copolymerized polymers illustrate this dependency, as the size of the POSS domains are alkyl-group dependent.
- Rheology of high molecular weight PDMS grafted with small amounts of POSS illustrates a dependence on both the POSS-alkyl-group and POSS shape.

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